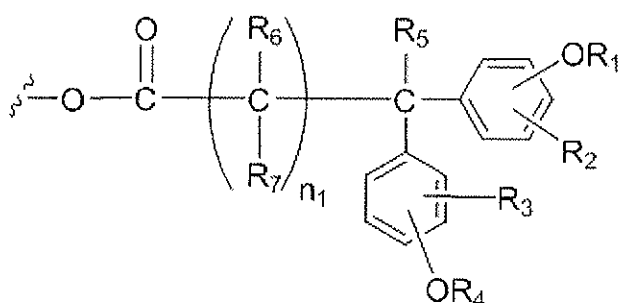


COMPOUNDS HAVING PHENOL SUBSTITUENTS, PROCESS FOR PRODUCING
THE COMPOUND, AND RESIST COMPOSITION COMPRISING THE COMPOUND

ABSTRACT

5 There are provided a novel compound having a phenol substituent represented
by the following formula (1), a method for producing the compound, and a resist
composition containing the compound.

[Formula 1]



10 wherein R_1 to R_7 and n_1 are as defined in the detailed description of the invention. The
substituent represented by the formula (1) contains an acid-dissociable functional group.

The compound having the phenol substituent represented by the formula (1)
constitutes a resist composition together with a photoacid generator, and thereby provides
a resist composition which is excellent in sensitivity, resolution and line edge roughness,
15 and is capable of drawing ultrafine patterns.